



Session Title:	[ME2] EUV Lithography II
Session Date:	November 20 (Mon.), 2023
Session Time:	14:55-16:15
Session Room:	Room E (Sidney Room, 2F)
Session Chair	Dr. Changhyun Cho (ex. SK hynix, Samsung Electronics Co., Ltd., Korea)

[ME2-1] [Invited]

14:55-15:25

High NA EUV: Eco Systems & Requirements

Changmin Park, Heeyoung Koh, Taehoi Park, Ilhwan Kim, Kyoungwan Yoo, and Jinsung Lee (Samsung Electronics Co., Ltd., Korea)

[ME2-2] [Invited]

15:25-15:55

EUV Application for Memory Devices

Changhyun Cho (ex. SK hynix, Samsung Electronics Co., Ltd., Korea)

[ME2-3]

15:55-16:15

Cleaning of Contaminated EUV Optics Using 172 nm Radiation

Jaeyeong Kim, Sanghun Ok, Haekweon Jung, Artem Rykov, and Donggun Lee (ESOL Inc, Korea)